

XA-7889A Re
PATENT APPLICATION

IN THE UNITED STATES PATENT AND TRADEMARK OFFICE

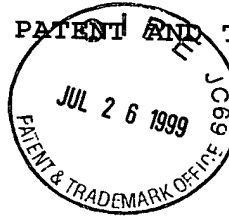
In re the application of:

Kenji NISHI

Appln. No.: 08/994,758

Filed: December 19, 1997

For: PROJECTION EXPOSURE APPARATUS



Group Art Unit: 2851

Examiner: A. Mathews

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Slange
8/4/99

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AMENDMENT

Assistant Commissioner for Patents
Washington, D.C. 20231

Sir:

In response to the Office Action mailed January 25, 1999, please amend the above-identified patent application as indicated below.

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TC 2800 MAIL ROOM

IN THE CLAIMS:

1 9. (Amended) A scanning exposure apparatus
2 comprising:
3 a scanning system for synchronously scanning a mask and
4 a photosensitive substrate at respective speeds which are
5 different from each other for scanning exposure; and
6 an adjusting system for moving the mask to decrease a
7 positional deviation between the mask and the substrate,
8 independently of scanning of the mask which is performed by
9 said scanning system, during the scanning exposure.

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